

# Tuning Thermal Boundary Conductance of 2D-Substrate Interfaces by Electrostatic Forces

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**Abstract**—Despite their potential for miniaturization, electronic devices made of 2D materials face thermal management challenges due to their reduced dimensionality, which can limit their efficiency and lifespan. Low thermal boundary conductance (TBC) is one major limiting factor in realizing efficient heat transfer to the substrate. Due to the roughness at the interface, the adhesion of 2D materials to their substrates tend to be weak, resulting in low TBC. Therefore, to improve heat flow from the 2D material, we need to discover novel ways of increasing TBC. In this study, we have used a numerical model combined with first-principles DFPT simulations to investigate a possible method to increase TBC using an electrostatic field due to gate voltage. Our study shows that electrostatic pressure can be used to effectively enhance TBC for an interface formed by a 2D material and a rough substrate. We find that electrostatic pressure can improve TBC by more than 300 % when an electric field of 3 V/nm is applied. This is due to an improvement in the vdW spring coupling constant, which shows a more than two-fold increase when a substrate roughness of 1.6 nm and correlation length of 10.8 nm, 2D-material's bending stiffness of 1.5 eV, and adhesion energy of 0.1 J/m<sup>2</sup> were used. We show that TBC is enhanced more when the substrate has a large roughness and small correlation length, and the 2D material has a large bending stiffness. This is because a stiff 2D sheet resist bending when voltage/pressure is applied, thus causing it to press more on the roughness peaks, resulting in a tremendous increase in the coupling constants at the peaks in the atomically rough surface of the substrate. However, a flexible 2D material can easily bend to conform to the topography of the rough substrate when voltage/pressure is applied, which makes the coupling constants across the interface more uniform. Here we show that TBC is enhanced more when adhesion is weak because a weak vdW bond is easily compressed by external pressure. Therefore, our study provides valuable information that can be applied in designing electronic devices with efficient heat management by using gate voltage, substrate roughness combined with the mechanical properties.

## I. INTRODUCTION

Due to their unique properties 2D materials have a wide range of potential application. Their unique properties make them attractive for application in nanoelectronics [1] and nanophotonics [2]. Their small thickness enables the miniaturization of electronic devices. However, the small size increases the density of components in integrated circuits, causing significant heating problems which prevent us from fully utilizing the advantages of 2D materials. Efficient heat dissipation from electronic device is therefore, vital for the continued miniaturization and integration of electronic devices. Low thermal boundary conductance

( $G$ ) of the 2D-substrate interfaces is a key bottleneck to the realization of efficient thermal management in devices based on 2D materials [3]. Roughness at the interface determines how well a 2D material can conform to the substrate and influences the 2D-substrate van der Waals (vdW) bond, affecting phonon coupling [4], [5]. This influences  $G$  since the stiffness of the vdW bond and the area of real contact are major factors that influence heat flow across interfaces [6], [7].

Heat is transferred across the interface by vertical flexural phonons through van der Waals (vdW) coupling between the 2D material and substrate. Thus, a change in the stiffness of the interface bond is expected to influence  $G$ . For instance, using hydrostatic pressure, various research groups have demonstrated that external pressure can be used to modulate  $G$  [8], [9], [10], [8]. Applying pressure can increase the weak vdW bond to values similar to that of strongly bonded, clean interfaces, hence improving  $G$  [11], [12]. It has been shown that hydrostatic pressure of up to 1 GPa can improve  $G$  of h-BN/SiO<sub>2</sub> and graphene/SiO<sub>2</sub> interfaces by 2-3 times [8]. Like hydrostatic pressure, electrostatic field due to gate voltage ( $V_g$ ) can produce a pressure ( $P_{elec}$ ) that can modulate phononic heat flow across interfaces [13], [11], [10], [14], [15]. However, despite the reported impact of pressure on  $G$ , there are significant gaps in the current understanding of the underlying physics of how  $P_{elec}$  influences  $G$  of interfaces formed by 2D materials and rough substrates. For instance, the contribution of mechanical properties of 2D materials and the substrate roughness to the impact of  $P_{elec}$  on  $G$  is lacking. A comprehensive investigation of the interplay between the mechanical properties of 2D materials, substrate roughness, and  $P_{elec}$  is necessary to provide a holistic understanding of the heat-flow mechanism across 2D-substrate interfaces.

Therefore, to address this issue, we have employed a numerical modelling together with first-principles DFPT simulations to study the impact of  $P_{elec}$  on  $G$  of interfaces formed by 2D materials and rough substrate. Our study shows that  $P_{elec}$  can improve  $G$  by more than 300 % when an electric field of 3e+9 V/m is applied. We find that  $G$  is enhanced more when the substrate has a large  $\Delta_{rms}$  and small  $L_{cor}$ , and the 2D material has a large bending stiffness ( $D_{bend}$ ) since a stiff 2D sheet resist bending when  $P_{elec}$  is applied thus causing it to press more on the roughness peaks. This causes a tremendous increase in  $K_s$  at the roughness peaks that leads to enhanced phonon coupling at the interface. However, a

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flexible 2D material can easily bend to conform to the topography of the rough substrate when  $P_{elec}$  is applied which makes  $K_s$  values across the interface more uniform. Thus, an interface formed by a stiff 2D material, shows many-large  $K_s$  values than that formed by one that is flexible when  $P_{elec}$  is applied. Besides, we show that  $G$  is enhanced more when  $\Gamma_0$  is weak because a weak vdW bond is easily compressed by  $P_{elec}$  resulting to a large increase in  $K_s$ . Therefore, our findings contribute to a better understanding of heat flow across 2D-substrate interfaces which will help in designing electronic devices with more efficient heat management.

## II. METHODS

In this study, we have designed a numerical model that utilizes phonon-dispersion data computed from first-principles Density Functional Theory (DFT) and Density Functional Perturbation Theory (DFPT) simulations, as implemented in the numerical code VASP. We have used graphene and SiO<sub>2</sub> substrate as our sample material. We model the adhesion of the 2D sheet on the atomically rough substrate as described in our earlier work [16]. Then, add  $P_{elec}$  due to applied  $V_g$ , as illustrated in Fig. 1. Applying  $V_g$  produce an electric field ( $F$ ) that induce a layer of charge in the 2D material. This result in an electrostatic force ( $F_{elec}$ ) between the 2D material and a gate which pull the 2D sheet toward the substrate.

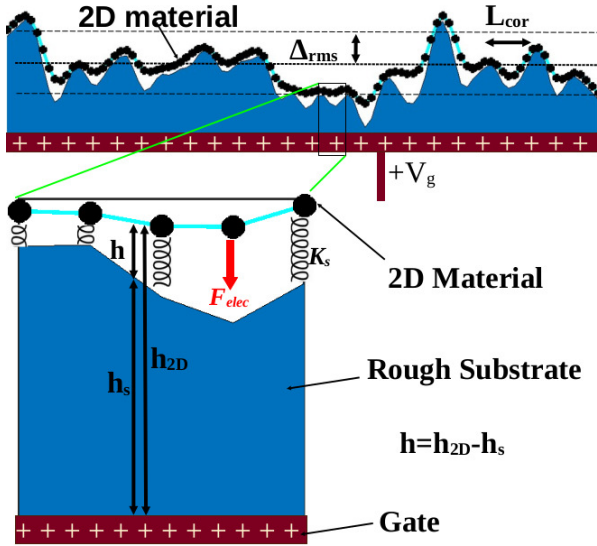


Fig. 1. A schematic showing a single layer of 2D material on a rough substrate and a gate. The 2D material cannot bend enough to conform fully to the rough substrate. We have regions that are in contact and others that are delaminated. This leads to variation in the 2D-substrate distance ( $h$ ) across the interface.

Here the electrostatic force is expressed as  $F_{elec}(h, V) = \frac{\epsilon A}{2} \left( \frac{V_g}{h_s + h} \right)^2$  then the electrostatic pressure is given by  $P_{elec}(h, V) = \frac{\epsilon}{2} \left( \frac{V_g}{h_s + h} \right)^2$ , where  $A$  is area,  $\epsilon$  is the dielectric constant of SiO<sub>2</sub> taken here as 3.7,  $V_g$  is the applied gate voltage,  $h_s$  is the thickness of the dielectric material, and  $h$  is the 2D-substrate distance

illustrated in Fig. 1. To get the total energy of the system, we calculate the sum of the vdW energy, bending energy, and the flexural energy as described in Ref. [16], and the energy due to electrostatic field expressed as  $U_{elec} = F_{elec} \times (h_s + h)$ . We then initialize the 2D-substrate distance to the equilibrium value for a flat substrate  $h_0$  taken here as 0.6 nm [17] and adhesion energy ( $\Gamma_0$ ) of 0.1 J/m<sup>2</sup> [17] then minimize the total energy by changing  $h$  using a quasi-Newton algorithm. This gives us the relaxed  $h$  values at every point in the interface. Using the optimized values of  $h$  we calculate  $K_s$  as described in our previous work [16]. Finally, we use a Landauer formalism that uses  $K_s$  values to find  $G$  at each interface point as described in Ref. [18], [16]. We determine the induced electron concentration by solving the quadratic relation  $en^2 - n\epsilon F - en_i^2 = 0$ , where  $e$  is the electron charge,  $n$  is the electron concentration,  $n_i$  is the intrinsic electron concentration, and  $F$  is the electrostatic field due to the applied  $V_g$ . Then the hole concentration,  $p$ , is calculated as  $p = n_i^2/n$ . Our model allows us to study the impact of  $P_{elec}$  on  $G$  and the contribution of roughness and the mechanical properties of the 2D material.

## III. RESULTS AND DISCUSSION

By applying a gate voltage, we induce a net charge concentration on the 2D material that causes an attractive force ( $F_{elec}$ ) that pull the 2D material towards the substrate. Unlike setups where hydrostatic pressure is used, here  $F_{elec}$  can cause the 2D sheet to bend and conform to the substrate roughness without destroying roughness peaks. As illustrated in Fig. 2(a),  $P_{elec}$  increases quadratically with increasing  $V_g$  while the square of induced net charge carrier density,  $(n - p)^2$ , varies linearly with  $V_g$ . Substrate roughness causes variations in  $h$  with some values being far larger than  $h_0$ . However, applying  $P_{elec}$  significantly reduces  $h$  values as shown in Fig. 2(b). As a result, a significant increase in the  $K_s$  is observed, as shown in Fig. 2(c). We note that  $K_s$  values at roughness peaks, which are already significant, are enhanced more when we apply  $P_{elec}$ . This leads to large improvement in  $G$  at these regions due to better phonon coupling, as shown in Fig. 2(d). However, due to the variation in  $h$  we observe disparities in  $K_s$  between different regions which leads to corresponding variations in  $G$  since it is proportional to  $K_s$  [18], [16].

Our analysis of  $K_s$  when an electric field of 3e+9 V/m is applied reveals that  $K_s$  increases linearly with the  $(n - p)^2$  and  $P_{elec}$  as shown in Fig. 3(a). We observe 244 %, 70 %, and 48 % increase in  $K_s$  for  $\Delta_{rms}$  of 1.6 nm, 0.9 nm, and 0 nm respectively and  $L_{cor}$  of 10.8 nm. Likewise Fig. 3(b) shows that  $G$  is also linear with  $(n - p)^2$  and  $P_{elec}$  which is in agreement with previous studies [13]. We observe an increase in  $G$  of 333 %, 92 %, and 80 % for interface with  $\Delta_{rms}$  of 1.6 nm, 0.9 nm, and 0 nm respectively and  $L_{cor}$  of 10.8 nm. The increase in  $G$  is because external pressure enhance phonon transmission

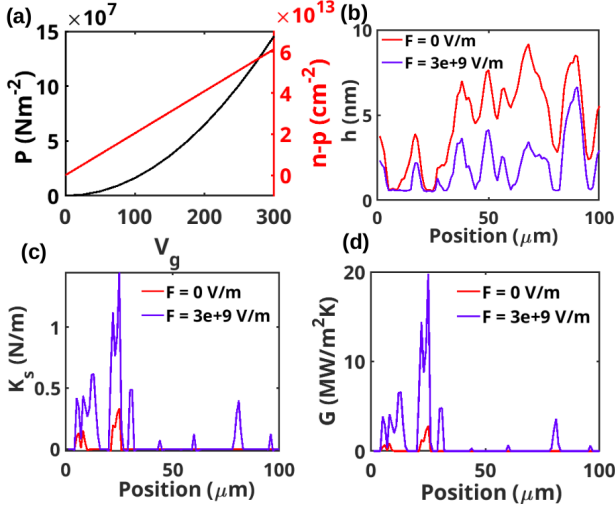


Fig. 2. (a)  $P_{elec}$  and  $(n-p)$  as a function of  $V_g$ . (b)  $h$ , (c)  $K_s$ , and (d)  $G$  as a function of position for a substrate with  $\Delta_{rms}$  of 2.5 nm and  $L_{cor}$  of 8.8 nm.

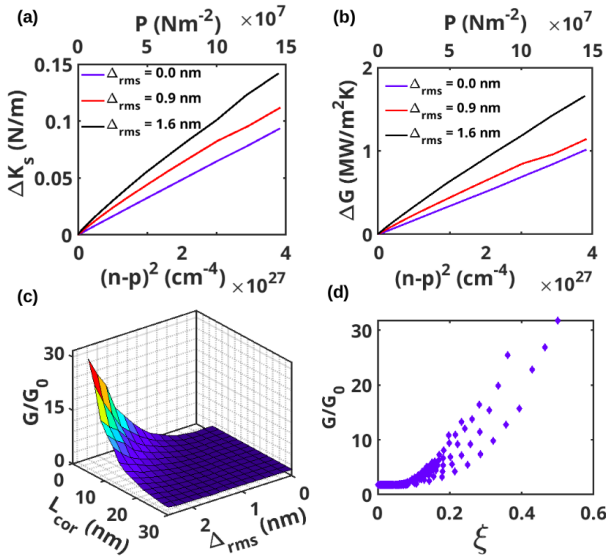


Fig. 3. Analysis of  $K_s$  and  $G$  at 300 K (a) the difference between  $K_s$  at an electric field of  $3e+9$  V/m and at 0 V/m,  $\Delta K_s$  and (b) the difference between  $G$  at an electric field of  $3e+9$  V/m and  $G_0$  at 0 V/m,  $\Delta G$  as a function of  $(n-p)^2$  and  $P_{elec}$  for interface with different  $\Delta_{rms}$  values and  $L_{cor}$  of 10.8 nm. (c) The ratio of  $G$  and  $G_0$  as a function of  $\Delta_{rms}$  and  $L_{cor}$ . (d) The ratio of  $G$  and  $G_0$  as a function of surface slope ( $\xi$ ).

across the interface. According to a previous study, this enhancement saturate when the vdW bond at the interface attain a stiffness similar to the stiffness of the bonds in the bulk of the individual materials [19]. However,  $P_{elec}$  is not large enough to achieve such a strong bond at the interface. As observed in Fig. 3(c),  $G$  increases more when  $\Delta_{rms}$  is large and  $L_{cor}$  is small, which implies that  $G$  is improved more when surface slope ( $\xi$ ), given by  $\xi = \Delta_{rms}/L_{cor}$ , is large as shown in Fig. 3(d). However, for small  $\xi$  values,  $G$  remains fairly constant before increasing almost linearly with increasing  $\xi$ .

To better understand the impact of substrate roughness on  $G$ , we analyze the effect of varying  $\Gamma_0$  since substrate roughness is expected to influence the adhesion between the 2D material and the substrate. We find that  $G$  is enhanced more when  $\Gamma_0$  is weak and the  $\xi$  is large as shown in Fig. 4(a). This is due to the fact that it is easier to compress the weak vdW bonds and significantly reduce  $h$  values increasing  $K_s$  which leads to an enhancement in  $G$ .

As shown in 4(b), we observe that  $G$  increases more when the bending stiffness of the 2D material ( $D_{bend}$ ) is large. This can be explained by considering how the 2D sheet interacts with a rough substrate; the large  $K_s$  values at the peaks of the roughness features dictate the heat flow across the interface, as seen in 2(c) and (d) and in our previous study [16]. If  $D_{bend}$  is small the 2D materials can easily bend to follow the topography of the rough-substrate surface which leads to a more uniform  $K_s$  values. However, if the 2D material has a large  $D_{bend}$ , applying  $P_{elec}$  pushes the 2D material towards the substrate so that the substrate distance at roughness peaks becomes very small; hence, we get very large  $K_s$  values at these regions. As illustrated in Fig. 4(c), we find that interfaces formed by stiff 2D material show many-large  $K_s$  values than that formed by a flexible material with small  $D_{bend}$ . Therefore,  $G$  is enhanced more when  $D_{bend}$  is large.

#### IV. CONCLUSIONS

In this study, we have demonstrated that electrostatic pressure ( $P_{elec}$ ) due to a gate voltage ( $V_g$ ) is a viable approach to improve thermal boundary conductance ( $G$ ) and, hence, thermal management in electronic devices made of 2D materials. We show that applying  $P_{elec}$  on graphene/SiO<sub>2</sub> interface can increase  $K_s$  by more than two-folds and cause  $G$  to increase by more than 300 % when an electric field of  $3e+9$  V/m is applied. Our study reveals that  $G$  is enhanced more when the substrate has a large  $\Delta_{rms}$  and small  $L_{cor}$ , and the 2D material has a large bending stiffness ( $D_{bend}$ ). This is because the vdW spring coupling constant ( $K_s$ ) at roughness peaks is large due to the small 2D-substrate distance ( $h$ ) at these regions. Therefore, at the roughness peaks we have better phonon coupling that enhance the overall heat flow across the interface. A stiff 2D sheet resist bending when  $P_{elec}$  is applied thus causing it to press more on the roughness peaks. This causes a tremendous increase in  $K_s$  at the roughness peaks that leads to even better phonon coupling. However, a flexible 2D material can easily bend to conform to the topography of the rough substrate when  $P_{elec}$  is applied which makes  $K_s$  values across the interface more uniform. Thus, an interface formed by a stiff 2D material, shows many-large  $K_s$  values than that formed by one that is flexible when  $P_{elec}$  is applied. Due to the roughness at the interface, the average adhesion of 2D materials to their substrates ( $\Gamma_0$ ) tend to be weak. Here we show that  $G$  is enhanced more when  $\Gamma_0$  is

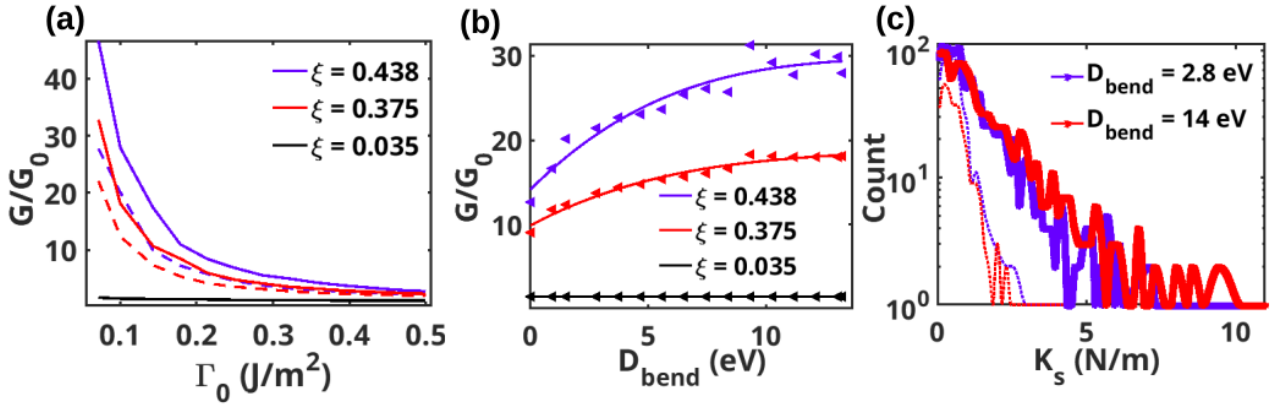


Fig. 4. (a) The ratio of  $G$  (at an electric field of  $3 \times 10^9$  V/m) and  $G_0$  (no electric field) as a function of  $\Gamma_0$  for  $D_{bend}$  of 1.5 eV (broken lines) and 13.24 eV (full lines) showing that  $G$  is enhanced more when  $\Gamma_0$  is weak and  $\xi$  is large. (b) The ratio of  $G$  and  $G_0$  as a function of  $D_{bend}$  for different values of  $\xi$  and  $\Gamma_0$  of 0.1 J/m<sup>2</sup> where the symbols show the data points and the line is a fit. We observe that  $G$  is enhanced more when  $D_{bend}$  and  $\xi$  are large. (c) The  $K_s$  values when an electric field of  $3 \times 10^9$  V/m is applied (full lines) and when there is no electric field (dotted lines) showing that in a stiffer 2D sheet, application of electric field leads to many-large  $K_s$  values than when the 2D sheet is flexible.

weak because a weak vdW bond is easily compressed by  $P_{elec}$  resulting to a large increase in  $K_s$ . Thus, our study demonstrates how gate voltage, substrate roughness, and mechanical properties of 2D materials can be leveraged to enhance thermal performance in electronic devices made of 2D materials.

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